

Amendments to the Specification:

Please replace paragraph [0004] on page 2 with the following amended paragraph:

[0004] Figure 1 shows a lithography system according to an embodiment of the invention.

Please replace paragraph [0005] on page 2 with the following amended paragraph:

[0005] Figure 2 shows components in a light source chamber according to an embodiment of the invention.

Please replace paragraph [0006] on page 2 with the following amended paragraph:

[0006] Figure 3 shows components in a light source chamber according to an alternative embodiment of the invention.

Please replace paragraph [0009] on page 3 with the following amended paragraph:

[0009] Figure 2 shows ~~the EUV chamber connected to the lithography chamber~~ components in a light source chamber according to an embodiment of the invention.

Please replace paragraph [0014] on page 5 with the following amended paragraph:

[0014] A plasma source may be used to generate the secondary plasma 220. For example, in the embodiment shown in Figure 2, an antenna (e.g., a coil) 225, with a radio frequency (RF) power supply 150 (Figure 1) to supply power to the coil. Other plasma sources may include, e.g., a helicon or ECR plasma source, DC glow discharge, or capacitive plate system.